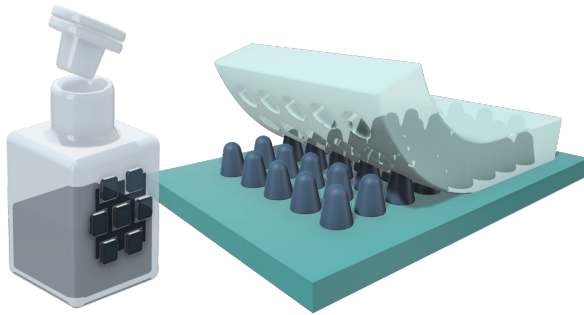


## ANTI-REFLECTION STRUCTURE FOR HIGH POWER LASERS

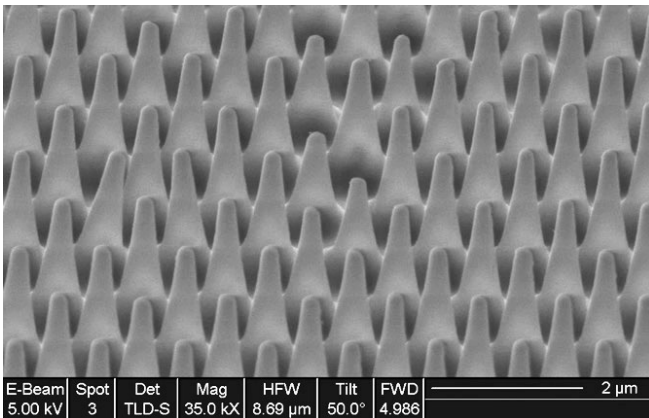
Metal oxide **INKS**

**NIL** process



**DIRECT PRINTING OF MOTH-EYE  
LIDT : > 150 J/cm<sup>2</sup> - 1060 nm - 12 ns**

**SOLNIL** printable inks can be framed in 3D structures atop glass, fused silica, sapphire, Si, Ge, etc. Broad-band and wide angle, moth-eye anti-reflection coatings can withstand high laser fluxes from femtosecond to nanosecond and CW.



E-Beam	Spot	Det	Mag	HFV	Tilt	FWD	
5.00 kV	3	TLD-S	35.0 kX	8.69 μm	50.0°	4.986	2 μm

### CHARACTERISTICS

<b>Reflexion</b>	~ 0.15-0.25% /face
<b>Transmission (θ)</b>	> 98% up to 50°
<b>LIDT</b>	Close to Fused Silica
<b>Spectral bandwidth</b>	400 < λ < 800 nm 800 < λ < 1200 nm

**MATERIALS:**  
**SOLNIL** develops its own materials from inorganic inks. They have high transparency from near-UV to MWIR and optical constants finely adjustable: **n = 1.120-2.60**

